

Title (en)  
Wafer centering system.

Title (de)  
Wafer-Zentriervorrichtung.

Title (fr)  
Système de centrage pour plaquette.

Publication  
**EP 0508748 A2 19921014 (EN)**

Application  
**EP 92303111 A 19920408**

Priority  
US 68228591 A 19910409

Abstract (en)  
A system for positioning a wafer (12) at a station within a wafer processing system such that the center of mass of the wafer coincides with the center of the rotatable chuck (22) at the station. A signal representative of the position of the wafer with respect to the rotatable chuck is produced by a sensor (54) and is utilized to determine a vector which defines distance and direction of the centering error between the center of rotation of the chuck and the center of mass of the wafer. The chuck and wafer are rotationally indexed through an angle to align the foregoing vector with a line which approximates the arcuate path traversed by the center of mass of the wafer when it is subsequently conveyed within the system. A transfer arm (44) is utilized to convey the wafer through the foregoing arcuate path with respect to the chuck so that the center of mass of the wafer coincides with the center of rotation of the chuck when the wafer is subsequently placed on same. <IMAGE>

IPC 1-7  
**H01L 21/00**

IPC 8 full level  
**B65G 49/07** (2006.01); **H01L 21/677** (2006.01); **H01L 21/68** (2006.01)

CPC (source: EP KR)  
**H01L 21/67796** (2013.01 - EP); **H01L 21/68** (2013.01 - EP); **H01L 22/00** (2013.01 - KR)

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DE FR GB

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**EP 92303111 A 19920408**; JP 11543692 A 19920408; KR 920005746 A 19920407; TW 81102437 A 19920331